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Process Monitoring and Fault Diagnosis

Guest Editor:

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Deadline for manuscript submissions:

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Message from the Guest Editor

The aim of this issue is to present methodological, theoretical, and practical developments related to "Process Monitoring and Fault Diagnosis". Potential topics include but are not limited to the following:

- Early detection of process abnormality in industrial practice;
- Feature extraction of normality under multi-steady and non-steady states;
- Dynamics feature extraction under different control strategies;
- Root cause identification based on both process knowledge and data analytics;
- Integration of first principle model and data information;
- Application of machine learning methods;
- Soft sensor development;
- Data processing for feature extraction;
- Bottleneck analysis based on multiscale process data analysis;
- New method for batch process monitoring;
- Modeling and analysis of non-stationary signals;
- Metrics for fault detection











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Message from the Editor-in-Chief

Processes (ISSN 2227-9717) provides an advanced forum for process/system-related research in chemistry, biology, material, energy, environment, food, pharmaceutical, manufacturing and allied engineering fields. The journal publishes regular research papers, communications, letters, short notes and reviews. Our aim is to encourage researchers to publish their experimental, theoretical and computational results in as much detail as necessary. There is no restriction on paper length or number of figures and tables.

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